

# EUROPEAN PATENT OFFICE

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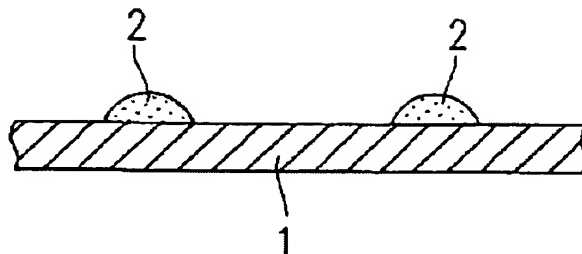
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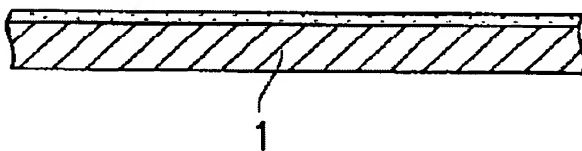
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TITLE : POLISHING PAD

(a)



(b)



ABSTRACT : PROBLEM TO BE SOLVED: To provide a polishing pad having increased polishing rate by improving the affinity of the slurry to the polishing pad.

SOLUTION: The polishing pad is made of a polyurethane composition. The polyurethane composition contains a urethane resin copolymerized with a compound having a hydrophilic group and the composition contains a hydrophilicizing agent. The hydrophilicizing agent is one or more compounds selected from 2,4,7,9-tetramethyl-5-decyne-4,7-diol-dipolyoxyethylene ether, 2,4,7,9-tetramethyl-5-decyne-4,7-diol and polymethylalkylsiloxane and the compound having a hydrophilicizing group is one or more compounds selected from ethylene oxide monomer, propylene oxide monomer and ethylene propylene oxide monomer.

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